Improving Short Chain PFAS Analysis using Reversed Phase Conditions

Conner McHale¹, Charles Powley², Barry Boyes¹, <u>Stephanie Rosenberg ¹</u> Advanced Materials Technology Inc., Wilmington, DE¹ Center for PFAS Solutions, New Castle, DE²

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INTRODUCTION

Per- and polyfluoroalkyl substances (PFAS) are a group of chemicals used to make fluoropolymer coatings and products that resist heat, oil, stains, grease, and water. These toxic "forever chemicals" are a concern to our health and environment and are now being regulated by the Environmental Protection Agency amongst other government agencies.

Short chain PFAS such as trifluoracetic acid (TFA) are challenging to separate due to low retention and poor peak shape. Some techniques such as mixed mode hydrophilic interaction liquid chromatography (HILIC) have been demonstrated to show improved retention, however, these techniques have their limitations.



LC/MS METHOD OPTIMIZATION

DryLab[®] software was utilized for method optimization to determine adequate retention and resolution for a panel of 18 per and polyfluorinated compounds which included "ultra-short" chain compounds.



Trifluoroacetic acid (TFA) is an organofluorine compound and considered an ultra-short chain perfluorocarboxylic acid (PFCA). One challenge analyzing TFA is achieving retention on column.



LC/MS Source Parameters

100

2

5

200

200

3

10

300

300

5

15

400

Figure 1: Common pathways for PFAS exposure released into the environment and health effects linked to PFAS

A new reverse phase, superficially porous particle (SPP) with a positive charge surface chemistry incorporated has shown separation advantages for short chain PFAS while using low ionic strength mobile phases such as formic/acetic acid.

HALO 90 Å PCS C18

• Excellent peak shape and increased loading capacity for basic compounds



formic acid conditions.







Figure 3: Optimization for TFA



Time [min]

REVERSE PHASE POSITIVE CHARGE SURFACE: FORMIC ACID

-						
000	<u>Conditions:</u>	MS System: Shimadzu 8045			I	Poak Identities.
7500	Column: HALO 90 Å PCS C18, 2.7 μm, 2.1 x 100 mm	MS CONDITIONS:			Π	reak identities.
	Guard Column: HALO [®] 160 Å PFAS Delay, 2.7 μm,	Detection: (-) ESI				1. TFA
- 	3.0 x 50mm	Spray Voltage: 3.5 kV				2 PFPrA
-	Mobile Phase: A: Water/ 0.1% Formic Acid	DL Temp: 300°C				
- 	B: Acetonitrile/ 0.1% Formic Acid	Neb. Gas: 2 L/min.	1			3. PFBA
-	Gradient: 0-20 min, 10% B, 20 – 25 min, 100% B	Dry 10 L/min.		I		4. PFPeA
0000	Flow Rate: 0.4 mL/min	Heat Block Temp.: 300°				
-	Temperature: 35 °C					5. PFHXA
- - 500	Wavelength: PDA, 260					6. L-PFBS
-	LC System: Shimadzu Nexera X2					

- Alternate L1 selectivity (PCS C18)
- Alternate L11 selectivity (PCS Phenyl-Hexyl)
- Built upon Fused-Core[®] technology for fast, efficient and reliable separations



SUPERFICIALLY POROUS VS. FULLY POROUS PARTICLES

Superficially Porous Particle (SPP)

Fully Porous Particle (FPP)



The design of the HALO[®] SPP with a solid core surrounded by a bonded phase shell provides higher efficiencies with less back pressure compared to FPP columns. These design advantages aid in meeting chromatographic requirements for PFAS methods.



3 mm x 10 cm C18 columns, 0.5 mL/min, 2 µL injection volumes (1:4 water:MeOH) MPA = 20 mM ammonium acetate, MPB = MeOH



REVERSE PHASE POSITIVE CHARGE SURFACE: ACETIC ACID





Figure 1: Comparison of peak asymmetry for PFBA and PFMA using FPP vs. SPP columns

PFAS compounds.

CONCLUSIONS

A new positive charge surface (PCS) stationary phase from Advanced Materials Technology shows adequate retention and peak shape for short chain PFAS analytes such as TFA and PFPrA in combination with a HALO[®] PFAS Delay column.

The superficially porous particle technology shows an advantage in peak shape when compared to fully porous particle material.

Requirement: Peak Asymmetry factor must be 0.8-1.5 (first two eluting compounds)

Future work will include LOD experiments along with temperature comparisons in order to speed up the analysis time. Moving the column dimension down to a 1.5mm ID will also be explored in order to increase signal intensity while reducing solvent consumption. HALO[®] is a registered trademark of Advanced Materials Technology, Inc

